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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.		
09/670,917 09/29/2000		Norikazu Mizuno	81877.0007	1895		
75	90 12/20/2001					
Hogan & Hartson L.L.P. Biltmore Tower Ste. 1900 500 S. Grand Ave. Los Angeles, CA 90071			EXAMINER			
			GUERRERO, MARIA F			
			ART UNIT	PAPER NUMBER		
			2822			

DATE MAILED: 12/20/2001

Please find below and/or attached an Office communication concerning this application or proceeding.

3					1.				
		Applicati n N		Applicant(s)					
Office Action Summary		09/670,917		MIZUNO ET AL.					
		Examiner		Art Unit					
,		Maria Guerrero		2822					
	of this communication app	pears n the c ve	er sheet with th	correspond nce ad	dress				
Period for Reply A SHORTENED STATUTO	PV DEBIOD FOR REPL	Y IS SET TO EX	PIRE 3 MONTH	(S) FROM					
THE MAILING DATE OF TI - Extensions of time may be available after SIX (6) MONTHS from the mail - If the period for reply specified above - If NO period for reply is specified ab - Failure to reply within the set or externorm - Any reply received by the Office late earned patent term adjustment. See	HIS COMMUNICATION. under the provisions of 37 CFR 1.1 ing date of this communication. e is less than thirty (30) days, a replove, the maximum statutory period nded period for reply will, by statute than three months after the mailin	136(a). In no event, how In within the statutory many will apply and will expine a cause the application	vever, may a reply be ti inimum of thirty (30) da e SIX (6) MONTHS fror to become ABANDON	mely filed ys will be considered timely in the mailing date of this co ED (35 U.S.C. § 133).	r. ommunication.				
Status									
1)⊠ Responsive to comm	nunication(s) filed on <u>29 </u>								
2a) This action is FINAL	<i>,</i> —	nis action is non-							
3) Since this applicatio closed in accordance	3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.								
Disposition of Claims									
4)⊠ Claim(s) <u>1-9</u> is/are p	ending in the application.	•							
4a) Of the above clair	n(s) is/are withdra	wn from conside	ration.						
5) Claim(s) is/are	allowed.								
6)⊠ Claim(s) <u>1-9</u> is/are re	jected.								
7) . Claim(s) is/are	objected to.								
8) Claim(s) are s	ubject to restriction and/o	or election requir	ement.						
Application Papers									
9) The specification is ob	jected to by the Examine	er.		·					
10) The drawing(s) filed o	n is/are: a)□ acce	epted or b)☐ obje	cted to by the Ex	aminer.					
	uest that any objection to th								
11) The proposed drawing	correction filed on	_ is: a)∏ appro	/ed b)□ disappı	roved by the Examina	er.				
If approved, corrected drawings are required in reply to this Office action.									
12) The oath or declaratio	n is objected to by the Ex	xaminer.							
Priority under 35 U.S.C. §§ 11	9 and 120								
13) Acknowledgment is r	nade of a claim for foreig	n priority under	35 U.S.C. § 119(a)-(d) or (f).					
a)⊠ All b)☐ Some * d	c) None of:								
1. Certified copie	s of the priority documen	ts have been red	eived.						
2. Certified copie	s of the priority documen	ts have been red	eived in Applica	tion No					
 Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 									
14) ☐ Acknowledgment is ma				•	l application).				
·	f the foreign language pr				- 121				
15) Acknowledgment is m									
Attachment(s)		_	7						
 Notice of References Cited (PTC2) Notice of Draftsperson's Patent Information Disclosure Statement 	Drawing Review (PTO-948)	· =	Notice of Informa	ry (PTO-413) Paper No I Patent Application (PT					

Application/Control Number: 09/670,917 Page 2

Art Unit: 2822

DETAILED ACTION

This Office Action is the first action on the merits.
 Claims 1-9 are pending.

Priority

2. Receipt is acknowledged of papers submitted under 35 U.S.C. 119(a)-(d), which papers have been placed of record in the file.

Specification

3. The title of the invention is not descriptive. A new title is required that is clearly indicative of the invention to which the claims are directed.

Claim Objections

4. Claims 5-7 are objected to because of the following informalities: claim 5 recites "has **such** a thickness"; claim 6 recites "to **such** an extent"; claim 7 recites the expression "or higher". Appropriate correction is required.

Claim Rejections - 35 USC § 112

The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

5. Claims 3-4 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

Application/Control Number: 09/670,917

Art Unit: 2822

Claims 3 recites "predetermined times". Claims 4 recites "predetermined thickness". The expression "predetermined" rendered the claims indefinite.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

6. Claim 9 is rejected under 35 U.S.C. 102(b) as being anticipated by Mori et al. (JP 06-080962) (Translation).

Mori et al. teaches an apparatus comprising a reaction container (Translation, claims).

Expressions relating the apparatus to contents thereof during an intended operation are of no significance in determining patentability of the apparatus claim." Exparte Thibault, 164 USPQ 666, 667 (Bd. App. 1969. A claim containing a "recitation with respect to the manner in which a claimed apparatus is intended to be employed does not differentiate the claimed apparatus from a prior art apparatus" if the prior art apparatus teaches all the structural limitations of the claim. Exparte Masham, 2 USPQ2d 1647 (Bd. Pat. App. & Inter. 1987).

Application/Control Number: 09/670,917

Art Unit: 2822

Claim R j cti ns - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 7. Claims 1-8 are rejected under 35 U.S.C. 103(a) as being unpatentable over Mori et al. (JP 06-080962) (Translation) in view of Moore et al. (U.S. 6,251,802).

Mori et al. teaches forming a silicon nitride film on a reaction container, removing silicon nitride film by introducing NF₃ gas. Mori et al. teaches the silicon nitride film is deposited by CVD using silane and NH₃. Mori et al. discloses the pressure ranging from several Torr to normal pressure (Translation).

Mori et al. fails to show forming the silicon nitride film with bis tertiary butyl amino silane and NH₃. However, Moore et al. shows forming a silicon nitride layer with bis tertiary butyl amino silane and NH₃ by chemical vapor deposition (col. 5, lines 25-35, col. 7, lines 3-15).

Mori et al. does not specifically show the reaction container being made of quartz. However, this is well known in the art.

Therefore, it would have been obvious to a person of ordinary skill in the art at the time of the invention to modify Mori et al.'s process by including the use of bis tertiary butyl amino silane as taught Moore et al. The modification would eliminate buildup of the silicon nitride layer on internal chamber parts and would produce less global warming gas effluents.

8. Claim 1 is rejected under 35 U.S.C. 103(a) as being unpatentable over Langan et al. (U.S. 5,413,670) in view of Moore et al. (U.S. 6,251,802).

Langan et al. teaches forming a silicon nitride film on a reaction container, removing silicon nitride film from a CVD reactor by introducing NF₃ gas (Abstract, col. 4, lines 3-10).

Langan et al. fails to show forming the silicon nitride film with bis tertiary butyl amino silane and NH₃. However, Moore et al. shows forming a silicon nitride layer with bis tertiary butyl amino silane and NH₃ by chemical vapor deposition (col. 5, lines 25-35, col. 7, lines 3-15).

Therefore, it would have been obvious to a person of ordinary skill in the art at the time of the invention to modify Langan et al.'s process by including the use of bis tertiary butyl amino silane as taught Moore et al. The modification would eliminate buildup of the silicon nitride layer on internal chamber parts and would produce less global warming gas effluents.

Conclusion

9. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Foster (U.S. 4,720,395) discloses a thermal CVD process for forming Si₃N₄. Hines et al. "Reducing Perfluorinated Compound Emissions " and Ino et al. "Plasma Enhanced In Situ Chamber Cleaning Evaluated by Extracted-Plasma-Parameter Analysis" teach using NF3 to clean chemical vapor deposition chambers.

Qiao et al. (U.S. 5,976,900) shows the use of quartz in the reaction container as well

Page 6

Application/Control Number: 09/670,917

Art Unit: 2822

known in the art (col. 8, lines 10-15). Xia et al. (U.S. 6,255,222) teaches a method for removing residue from substrate processing chamber.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Maria Guerrero whose telephone number is 703-305-0162.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead Jr. can be reached on 703-308-4940. The fax phone numbers for the organization where this application or proceeding is assigned are 703-308-7722 for regular communications and 703-308-7382 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

MG

December 10, 2001

CAR WITEEAD, JR.

TECHNOLOGY CENTER 2800